1	The role of lattice dynamics in ferroelectric switching
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30 Abstract:

Reducing the switching energy of ferroelectric thin films remains an important goal in 31 the pursuit of ultralow power ferroelectric memories and magnetoelectric spin-orbit 32 logic devices. Here, we elucidate the fundamental role of lattice dynamics in 33 ferroelectric switching by combining thermodynamic calculations, experiments, and 34 time-resolved phase-field simulations on both freestanding bismuth ferrite (BiFeO₃) 35 membranes and films clamped to a substrate. We observe a distinct evolution of the 36 ferroelectric domain pattern, from striped, 71° ferroelastic domains (spacing of ~100 37 nm) in clamped BiFeO₃ films, to large (10's of micrometers) 180° domains or even 38 single domain structures, in freestanding films. Through the use of piezoresponse 39 force microscopy, X-ray diffraction, polarization-electric-field hysteresis loops, and 40 high-speed pulsed ferroelectric switching experiments, it is found that by removing 41 the constraints imposed by mechanical clamping from the substrate we can realize a 42 ~40% reduction of the switching voltage and a consequent ~60% improvement in the 43 switching speed. Our findings highlight the importance of a dynamic clamping 44 process occurring during switching, which impacts strain, ferroelectric, and 45 ferrodistortive order parameters and plays a critical role in setting the energetics and 46 dynamics of ferroelectric switching. We reveal the fundamental importance of 47 considering all coupled order parameters (aforementioned) in the BiFeO₃ system, 48 and introduce the notion of "strain + tilt clamping" by a substrate. 49

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The last three decades have witnessed a significant interest in the science and 52 technology of ferroelectric thin films, driven by the fascinating fundamental physics of 53 the polar state in reduced dimensions as well as the technological applications, for 54 example, in nonvolatile memories[1], [2], which utilize the switchable nature of the 55 ferroelectric polarization to store information. In the case of proper ferroelectrics[3]-56 [6], where the spontaneous polarization arises from the freezing of a soft-phonon 57 mode at the Curie temperature, the coupling between the dipolar order and the 58 lattice is much stronger than, for example, the coupling of spins to the lattice in 59 ferromagnets[7]–[9]. Focusing on proper ferroelectrics such as BiFeO₃ (BFO), 60 PbTiO₃ (PTO), and BaTiO₃ (BTO) this strong coupling between the lattice and the 61 spontaneous electric dipoles means that switching of the polar state is accompanied 62 63 by a corresponding, dynamic lattice distortion during switching. It is widely believed that the fundamental limit on ferroelectric switching speed is thus set by the phonon 64 dispersion relation, and specifically the group velocity for acoustic phonons in the 65 system (*i.e.*, speed of sound), which sets a limit on how fast the lattice can respond. 66 For films clamped to a substrate, the substrate will undoubtedly modify the phonons 67 of the thin-film, altering their energetics and dispersion characteristics. For example, 68 a perovskite substrate that does not contain any oxygen-octahedral tilts will probably 69 soften (and reduce the equilibrium amplitude of) the O₆ tilts (ferrodistortive order 70 parameter) of a BFO film, which will in turn impact, and likely facilitate, ferroelectric 71 switching. In contrast, a perovskite substrate presenting rigid oxygen octahedral tilts 72 may harden the corresponding phonons of the film, and may act as a "built-in field" of 73

sorts for the BFO tilts; this will most likely result in slower switching, and potentially
even modify the switching pathway. Clearly, the substrate, and the mechanical
boundary conditions it imposes, plays a critical role in influencing the lattice
dynamics of the film.

Even if we restrict ourselves to simple considerations such as those just 78 mentioned – ignoring subtle effects related to phonon dynamics and their interplay 79 with polarization and strains – it is clear that this is an exceedingly difficult problem. 80 As such, we devise a tractable set of theoretical calculations and experiments that 81 aims to answer a question that addresses how lattice dynamics influence 82 polarization reversal, namely, what is the role of the substrate in influencing 83 ferroelectric switching? We begin by considering the clamping effect, or resistance to 84 structural deformation, which imposes an additional energy barrier that must be 85 overcome to induce switching in films constrained to a substrate. Such an enhanced 86 energy barrier can be understood as a coupling between the dynamic lattice strain 87 and the primary order parameters in the system, which manifests itself both in the 88 energy required to switch the state (coercive field) as well as in the switching time 89 (both nucleation and growth regimes of polarization reversal). Indeed, previous work 90 combining phase-field modeling with *in-situ* biasing transmission electron microscopy 91 to study mechanical and electrical loading of relaxor ferroelectrics has demonstrated 92 the importance of such mechanical constraints in establishing ferroelastic switching 93 energies [10], [11]. Here, we present a detailed theoretical and experimental analysis 94 of the role of substrate clamping in influencing ferroelectric switching in the proper 95

ferroelectric/multiferroic, BFO. While all thin-film ferroelectrics are subject to 96 clamping constraints from the substrate, it can play a larger role in inhibiting 97 ferroelastic switching pathways [12], [13]. BFO, which follows a two-step polarization 98 switching pathway, (consisting of out-of-plane (109°) and in-plane (71°) steps (Fig 99 1c.), with its ferrodistortive oxygen octahedral tilts following the ferroelectric 100 polarization [14], [15]) is therefore an ideal candidate for studying the role of 101 clamping in impacting the switching of coupled primary order parameters. Previous 102 theoretical works have developed highly successful theories for the equilibrium 103 energetics of the BFO system, including effects from oxygen octahedral tilting [16], 104 [17], though they have not addressed how substrate clamping influences such 105 energetics (or dynamics) of the switching process. We theoretically study varying 106 degrees of clamping, and introduce the notion of "strain + tilt clamping" where the 107 substrate influences not only the ferroelectric and strain order parameters, but also, 108 importantly, the oxygen octahedral tilts. We show that "strain clamping" alone 109 (ignoring the role of the substrate in clamping the ferrodistortive order) is insufficient 110 to explain the changes to the energetics and dynamics of switching in freestanding 111 vs clamped BFO films, which we observe in our experiments. Interestingly, phase 112 field calculations reveal that the rotation of the ferrodistortive order slows the 113 switching by almost an order of magnitude in comparison to the case where oxygen 114 octahedral tilts are ignored. Our findings are further complemented by similar 115 measurements in the literature [18] on thin films of ferroelectric BTO, a prototypical 116 tetragonal ferroelectric, a finding which highlights how substrate clamping impacts a 117

variety of ferroelectric materials. In the case of BTO [18] and in the present study, the
data reveal a clear impact on the switching voltage (a measure of the barrier energy)
as well as the switching dynamics (as manifested by changes in the switching time).
These observations indicate that the effects from mechanical clamping by the
substrate are broadly applicable to all displacive ferroelectrics. Such an
understanding is essential, as the 100 mV switching voltage goal remains a grand
challenge for the field[1], [2].

While there have been a large number of studies of quasi-static switching 125 behavior and equilibrium properties of thin films[19]-[23], there have been fewer 126 studies of the limits and timescales of fast switching[24]-[28], and even fewer on the 127 role of substrate clamping effects in influencing ferroelectric switching below 1µs 128 [18]. A key question is how to quantify the role of the substrate in dictating the 129 switching process and whether switching can be studied experimentally without the 130 influence of the substrate. Freestanding ferroelectric membranes have recently 131 emerged as an exciting platform to study the role of mechanical constraints in 132 ferroelectric systems[29], and here, we attempt to quantitatively address the effect of 133 mechanical clamping by using a combination of thermodynamic calculations, phase-134 field simulations, piezoresponse force microscopy, and quasi-static and dynamic 135 switching measurements on epitaxial, substrate-attached and freestanding versions 136 of the same thin films (Fig 1a.). 137

¹³⁸ To quantitatively understand the switching-energy landscape with and without ¹³⁹ substrate clamping in BFO (**Fig. 1b**), we modeled the thermodynamic free-energy within the context of the Landau theory for ferroelectrics [30]–[32], using a potential
of the form:

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$$f = \alpha_{ij}p_ip_j + \alpha_{ijkl}p_ip_jp_kp_l + \beta_{ij}\theta_i\theta_j + \beta_{ijkl}\theta_i\theta_j\theta_k\theta_l + t_{ijkl}p_ip_j\theta_k\theta_l + \frac{1}{2}C_{ijkl}(\epsilon_{ij} - 143 \quad \epsilon_{ij}^0)(\epsilon_{kl} - \epsilon_{kl}^0)$$
(1)

[33] where p_i , θ_i , and ϵ_{ii} refer to the ferroelectric polarization, ferrodistoritve rotation 144 of the oxygen octahedra, and strain, respectively, while $\epsilon_{ij}^0 = \lambda_{ijkl}\theta_k\theta_l + Q_{ijkl}p_kp_l$. 145 Additional details are provided in Methods and Supporting Information Section 1, 146 Section 2. We use two sets of parameters for this Landau potential: a first set 147 directly fitted to first-principles results[34] (nominally at 0 K) and a second one 148 corresponding to the room-temperature Ginzburg-Landau potential for BFO 149 previously introduced in [33], the latter of which is the same model used for the 150 phase-field simulations of ferroelectric switching discussed below. Guided by 151 previous literature[14], [35], we know that upon the application of an out-of-plane 152 electric field, BFO typically undergoes 180° switching via a two-step process (Fig. 153 **1c**): a 109° switch (where the out-of-plane polarization component reverses together 154 with one in-plane component) followed by a 71° switch (where the remaining in-plane 155 component reverses), or vice versa. In our thermodynamic analyses, we calculate 156 the free-energy profile associated with the two switching steps while considering 157 different levels of clamping. 158

First, we calculate the case of no clamping, or the "membrane" case. The energy profiles labeled "membrane" (blue curves in **Fig. 2**) are obtained by continuously varying the transformed polarization components (P_y and P_z for the 109° step, P_x for the 71° switch) while allowing all other variables (remaining polarization components, tilts and strains) to adapt to this change. We observe, as expected[12], [15], [36], that the tilts reverse together with the polarization. This yields the lowest-energy switching paths corresponding to the experimental case of a free-standing membrane.

Next, we consider the case of the so-called "strain clamping". In order to 167 separate clamping effects from the effects of epitaxial misfit strain, we assume the 168 169 film is thick enough so that it is fully relaxed to its rhombohedral ground state. The fully relaxed nature of the film does not, however, mean that it is free to deform; on 170 the contrary, it is still clamped and, as dictated by the substrate, energetically favors 171 maintaining its original state. To obtain the free energy profiles labeled "clamped" in 172 **Fig. 2a(b)**, **2e(f)** we vary P_v and P_z for 109° switch (P_x component for 71° switch) 173 while keeping the strains $\epsilon_{11}, \epsilon_{22}$ and ϵ_{12} fixed to their equilibrium values 174 corresponding to the initial polarization direction (before the initial 109° out-of-plane 175 switch). All the other order parameters are allowed to relax following the polarization 176 177 switching process (Methods). One can see that strain clamping leads to slightly increased energy barriers compared to the freestanding case, about 6% for the 109° 178 step and 20% for the 71° step. Notably, the results obtained for the first-principles 179 Landau potential (Fig. 2a and 2b) and the phenomenological model (Fig. 2e and 2f) 180 are essentially equivalent with regards to the change in activation energy barriers, 181 highlighting the consistency of both methods. Additional free-energy calculations for 182

the prototypical ferroelectrics PTO and BTO are presented for clamped and membrane cases (**Fig S1**). These calculations, consistent with previous experimental work [18], show a similar reduction in switching energy for freestanding membranes compared to clamped films suggesting a broad applicability of the role of strain clamping effects in ferroelectric switching.

There exist other ways in which the substrate can impact switching, namely by 188 clamping additional order parameters (such as octahedral tilts) beyond strain. This 189 can arise, for example, by a mismatch in roto-strictive coefficients between the film, 190 191 electrode, and substrate. To quantify this effect, we introduce "strain + tilt clamping" (and varying degrees, *i.e.*, weak vs strong, thereof) and compute the free-energy 192 profiles while imposing additional constraints on some order parameters in our 193 simulations. In the limiting case of "strong strain + tilt clamping" (Fig **2g**, **2h**) we fix all 194 non-switching polarization and tilt components (as well as $\epsilon_{11},\epsilon_{22}$ and $\epsilon_{12})$ to their 195 equilibrium values corresponding to the initial polarization direction. Moreover, we do 196 not fully relax the switching tilt components, but interpolate them between the values 197 corresponding to the minima of the free energy curves (Methods). Only strains 198 $\epsilon_{33}, \epsilon_{13},$ and ϵ_{23} are allowed to relax following the variation of the other order 199 parameters. One can see that clamping of other degrees of freedom immediately 200 results in a greater difference between the membrane and clamped cases (about 201 64% for both the 109° and 71° steps for the phase-field parameter set). We expect 202 the true clamping effects to lie between "strain clamped" and "strong strain + tilt 203 clamped" cases, which serve as limiting cases of clamping effects. To quantify such 204

an intermediary degree of clamping, we consider a third type of clamping termed "weak strain + tilt clamping." In this case, (**Fig. 2b, 2c, 2g, 2h**) we fix the nonswitching tilt components, but allow switching tilt components to adapt freely to the change in polarization. In this case we see a smaller reduction in the energy barrier upon releasing the film from the substrate, which more accurately describes our experimental data, discussed below.



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Figure 1. **Role of Clamping**. **a**. Transmission electron microscope (TEM) image of SRO/BFO/SRO heterostructure. **b**. Schematic highlighting significant mechanical constraints imposed by the substrate compared with the freestanding film. **c**. SRO/BFO interface schematic showing ferrodistortive oxygen octahedra rotations and switching pathway (109° out-of-plane followed by 71° in-plane) for BFO films.

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To experimentally study the effect of clamping imposed by the substrate, we employ recent advances in chemically assisted lift-off techniques to produce freestanding BFO layers. Such techniques are rapidly emerging as an approach for

tuning the lattice distortion and strain in ferroelectrics[37]-[43]. Several sacrificial 221 layers have been developed, such as water soluble Sr₃Al₂O₆[39], acid solution 222 soluble La_{0.67}Sr_{0.33}MnO₃ (LSMO)[40], and graphene for mechanical exfoliation[42], 223 leading to freestanding ferroelectric films down to the monolayer limit[29], as well as 224 integration of single-crystalline membranes[42], and flexible layers with super-225 elasticity[43]. We demonstrate that quantitatively different features are obtained in 226 freestanding BFO membranes versus their clamped counterparts, both in quasistatic 227 measurements of the energetics (coercive field from hysteresis measurements) and 228 dynamical measurements (pulsed switching studies) of the switching process. 229

Two types of samples were employed for this study. The first type, henceforth 230 referred to as "clamped", is a Pt (20 nm)/SrRuO₃ (SRO 30 nm)/BFO(x nm)/SRO(30 231 nm), (where x ranges from 12.5 nm to 100 nm) heterostructure (Fig 1a) epitaxially 232 grown via pulsed-laser deposition (PLD) on SrTiO₃ (STO)₁₀₀₁₁ substrates (Methods). 233 The second sample type, henceforth referred to as a "membrane", is a 234 Pt/SRO/BFO/SRO/LSMO stack, that has been subsequently released from the 235 STO₁₀₀₁₁ substrate by etching the LSMO layer (Supporting Information **Fig. S2**) [40] 236 237 to completely lift-off the Pt/SRO/BFO/SRO stack from the STO substrate. A supportive PDMS layer is used to then transfer the stack to a Pt/Si (001) substrate. 238 We use an etch rate of ~1 nm/hour to dissolve the LSMO layer in order to avoid 239 deformation or damage of the Pt/SRO/BFO/SRO heterostructure during lift-off. To 240 verify a successful transfer, we measured via atomic force microscopy (AFM) the 241 surface roughness of the initial film and that of the transferred freestanding 242

membrane. Typical measurements are shown (Supporting Information Fig. S2b and
S2c), yielding a surface roughness of 223 pm and 406 pm, respectively, indicating
that the high-quality samples can be maintained during this process.

The out-of-plane (c) and in-plane (a) lattice parameters of the films both before 246 and after lift-off were extracted from X-ray diffraction (XRD) line scans and reciprocal 247 space maps (RSMs). The diffraction results show that the freestanding membranes 248 still possess good epitaxial relationships between BFO and SRO layers (Supporting 249 Information Fig. S3). The c and a lattice-parameter values of the BFO layers 250 calculated from the XRD scans are provided as a function of BFO thickness (Fig. 3). 251 We clearly observe that the in-plane lattice constant, a, increases and the out-of-252 plane lattice constant, c, decreases after the film is released from the substrate. This 253 evolution is succinctly captured by a reduced c/a ratio compared to the epitaxial BFO 254 films on substrates. The change in c/a for samples with BFO thickness of 8, 35, 60 255 and 100 nm is in the range of 1.4%-1.9% (Fig. 3a), suggesting that the spontaneous 256 distortion, and therefore polarization of BFO membranes is smaller, and the 257 switching-energy barrier between adjacent polarization states 258 should be correspondingly reduced[44]. Notably, the 100-nm-thick BFO clamped film has an in-259 plane lattice constant (a = 3.95 Å) close to its bulk value (a = 3.96 Å)[45], indicating 260 the clamped film is nearly completely relaxed and that effects from misfit strain (-1.35%) 261 when grown on STO)[46] are minimized at this thickness. 262



Figure 2. Thermodynamic calculation of switching free energy for BFO. a. (e.) 264 and b. (f.) show 109°, out-of-plane, and 71°, in-plane, switching energy landscapes, 265 respectively, calculated using Landau coefficients obtained from DFT (used in the 266 phase-field model, Supporting Information Section 1) for the strain-clamped and 267 membrane cases. c. (g.) and d. (h.) show 109° and 71° double well potentials, 268 respectively, calculated using the Landau potential from DFT (from the phase-field 269 model) for strain + tilt clamped and membrane cases. In all panels, the "membrane" 270 curves (blue) correspond to a film free of constraints, i.e. all order parameters are 271 free to adapt to the switching polarization. To obtain the "clamped" (solid orange 272 curves) results in panels a., b., e., and f., the in-plane strains are held fixed, 273 modeling the effect of strain clamping from the substrate. "Clamped (Weak)" (solid 274 orange) curves in **c.**, and **d.**, (**g.**, and **h.**) represent switching potentials derived from 275 DFT parameters (phase-field parameters), but subject to so-called "weak strain + tilt 276 clamping" constraints, where, additionally, all non-switching polarization and tilt 277 components are held fixed. "Clamped (Strong)" (dashed orange) curves in c., and d., 278 (g., and h.) show switching potentials derived from DFT parameters (phase-field 279 parameters), but subject to so-called "strong strain + tilt clamping" constraints, 280 where, all the non-switching polarization and ferrodistortive components are held 281 fixed and the switching components of tilts are linearly interpolated between the 282 values corresponding to the minima of the free-energy curves. Percentages listed 283 are reductions in maximum energy barrier for membrane vs. clamped films in each 284 scenario. Calculations correspond experimentally to the thickest, fully relaxed, films. 285 In the "strain clamping" case, the in-plane strains are fixed to their values in the initial 286 state, before the 109° switch occurs. Hence, the fixed strains cannot adapt to the 287 new polarization state after the 109° switch and, therefore, the resulting state has 288 higher energy than the initial one. This results in the asymmetric shape of the free-289 energy curves (in the case of "strain+tilt clamping", in addition to in-plane strains, the 290 non-switching polarization and tilt components are fixed as well). Note that this effect 291 is more pronounced in the simulations using the phase-field model parameter set 292 (panels e-h) compared to the DFT one (a-d). This occurs because the relative 293 294 magnitude between the C_{iikl} parameters (entering the strain-related terms in Eq. 1) and the other model parameters in the phase-field set is higher compared to the DFT 295 set which leads to the stronger predicted clamping effect. 296

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The impact of mechanical constraints from the substrate can be observed 297 directly in piezoresponse force microscopy (PFM) imaging of the ferroelectric domain 298 structure before and after release from the substrate. In-plane and out-of-plane PFM 299 amplitude images for both the clamped BFO and freestanding membrane (Fig 3b,c, 300 Supporting Information S4a,b), reveal dramatic differences. The well-ordered 71° 301 stripe domain pattern of BFO in the clamped film evolves into a "blocky" 180° domain 302 pattern with a larger domain size in the freestanding membrane. These changes are 303 also observed in the corresponding in-plane and out-of-plane PFM phase 304 305 (Supporting Information Fig. S4c-f) images for the clamped film and membrane. Kittel's law[47] for ferroelectric domains states that the domain width scales as: 306

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$$w = \sqrt{\frac{\sigma t}{U}}$$
 (3)

where σ , t, and U are the domain-wall energy, film thickness, and domain energy, respectively. The domain-wall energy is given by:

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$$U = U_{dip} + U_x + U_e$$
 (4)

where U_{dip} , U_x , and U_e are the energy contributions from dipolar interactions (correlation energy), elastic energy, and depolarization energy, respectively[6]. By releasing the film from the substrate, we significantly reduce the elastic energy (correspondingly leading to an increase in the domain width), and therefore the electrostatic energy becomes the dominant energy scale. In order to minimize electrostatic energy, ferroelectric domains typically adopt configurations such that $\nabla \cdot P \approx 0$ at domain-wall boundaries, and such a condition is satisfied with 180°

domains in perovskite ferroelectrics[6]. We directly observe this effect here, 318 highlighting the dominance of electrostatic energy after removal of elastic constraints 319 from the substrate. It is important to note that the changes in domain structure 320 observed (Fig. 3) can be unequivocally attributed to the role of substrate clamping. 321 In both the clamped and freestanding cases, the SRO layer is the same thickness 322 (30nm), so, while the SRO layer may play a small role in epitaxially constraining the 323 BFO, its effect is present in both the clamped and freestanding cases. Therefore, any 324 differences we observe between these two cases can be attributed to the substrate 325 clamping alone, and not to the SRO layer. Additional PFM images of BFO samples 326 with thickness of 60, 35, 20 and 8 nm, before and after lift-off are shown (Supporting 327 Information Fig. S5). Interestingly, irrespective of the domain structure of the 328 clamped film (*i.e.*, either pure 71° domains or a mixture of 71° and 109° domains), all 329 freestanding membranes feature larger domain sizes and the emergence of an 330 exclusively 180° domain pattern, concomitant with the disappearance of the 71° and 331 109° domains. 332

Our experimental PFM results are in good agreement with the mesoscale domain structure predicted by phase-field simulations, calculated using the same Ginzburg-Landau potential [33] as that used to calculate free-energy switching landscapes (**Fig. 1**) and including gradient terms to account for domain configuration evolution (Methods). While the 100-nm-thick clamped films (**Fig. 3b**) exhibit twovariant stripe domains, thinner films (Supporting Information **Fig. S5**) exhibit fourvariant domain structures. To model the domain structure evolution, we employed

phase-field simulations using both four-variant (Fig. 3d and 3e) and two-variant 340 initial domain structures (Supporting Information Fig. S6). As observed in our 341 simulations, by releasing the film from the substrate, the lateral width of the domain 342 indeed increases dramatically, and 180° domain walls emerge in the freestanding 343 membranes (Fig. 3e and Supporting Information S6c,d). There are two important 344 considerations in understanding the observed domain structure evolution: misfit 345 strain and the clamping effect from the substrate. To disentangle the two effects, and 346 specifically elucidate the role of clamping in the system, we turn to experimental 347 measurements of the energetics and dynamics. 348



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Figure 3. Lattice parameters and domain structure of the BFO clamped films and freestanding membranes. a. c and a lattice parameters and their ratio c/a for the BFO films and membranes as a function of thickness. The freestanding BFO membranes exhibit decreased c, increased a, and decreased c/a ratio. b., c., Inplane PFM amplitude image of 100-nm BFO film (b.) and freestanding membrane (c.). d., e., Phase-field simulation of BFO layer before (d.) and after lift-off (e.).

356 The measurements of polarization versus applied voltage (P-V) hysteresis loops 357 on both the clamped films and freestanding membranes were carried out at low

temperature (100 K) to minimize the effects of leakage. We compare P-V hysteresis 358 loops measured at 10 kHz for 100-nm and 35-nm BFO clamped films (orange) and 359 membranes (blue) (Fig 4a and Fig 4b). The data demonstrate that the coercive 360 voltage, defined as the voltage at which the average polarization is zero, measurably 361 decreases upon lift-off. The free-standing membranes also have a lower remnant 362 polarization, consistent with the observed decrease in c/a ratio (Fig 3a). Frequency 363 dependent P-V loops were measured (Supporting Information Fig S7 and Fig S8) 364 showing less-dispersive, and distinctly lower coercive voltages for the freestanding 365 membranes when compared to the clamped films. Both 100-nm and 35-nm BFO 366 samples show a significant decrease (~40%) in the coercive voltage after the lift-off 367 process; indeed, this is a general feature of all the thicknesses that we studied (down 368 369 to at least ~25 nm; measurements below this thickness were hampered by shorting issues and the mechanical stability of the free-standing membranes). The 370 polarization behavior under applied voltage for both clamped and freestanding films 371 was further investigated via PFM-based piezoelectric-hysteresis (both phase and 372 amplitude) loops at room temperature. We can observe a distinct decrease of the 373 switching voltage by ~40% for the samples after lift-off (Supporting Information Fig. 374 **S9**), consistent with our P-V hysteresis loop measurements at low temperature. It is 375 important to note that, while the 100-nm-thick clamped film is known to be almost 376 fully relaxed (Fig 3a), reductions in switching energy persist even at this film 377 thickness, indicating that clamping, and resistance to structural distortion during 378 *switching*, plays a dominant role in setting the switching energetics over effects from 379

misfit strain. The coercive voltage is a measure of the energy required to switch the 380 polarization, and our observed coercive voltage ratio (~40%) between free-standing 381 and clamped films indicate that the clamping effect lies somewhere between the 382 limiting cases of strain clamping and strong strain + tilt clamping, and is most 383 accurately described by weak strain + tilt clamping (Fig. 2). This is an important 384 finding, and deserves special attention. Strain clamping alone, where the mechanical 385 effect of the substrate only inhibits switching via the strain order parameter, is 386 insufficient in explaining the dramatic reduction in energy observed experimentally. 387 388 The substrate clamping plays an additional role, namely that the mechanical constraints imposed also inhibit variation of oxygen octahedral tilting. Only when 389 both effects are considered, can we explain the significant reduction in switching 390 391 energy observed. Furthermore, the extreme case of strong strain + tilt clamping predicts a reduction in energy larger than that observed. This indicates that while 392 clamping effects during switching inhibit changes in octahedral tilting, they do not 393 completely prevent these changes from occurring. 394

Having established the role of clamping on switching energetics, we now turn to the dynamics of the switching process. Polarization reversal in ferroelectric thin films is known to proceed via nucleation and growth of reverse polarized domains[21], [24], [48], [49] and we used pulsed ferroelectric measurements[24] to directly measure the ferroelectric polarization evolution during switching. We show polarization transients for various applied voltages for a 25-nm-thick clamped film and freestanding membrane (**Fig. 4c**, Supporting Information **Fig. S10a** and **S10b**

show corresponding observed ferroelectric switching displacement current). It is 402 known that the dynamical timescale of free-charge in the measurement circuit, 403 namely RC (resistance×capacitance) time, plays a significant role in the ferroelectric 404 switching times observed in macroscopic device structures at these timescales[24] 405 because the RC-time of the measurement circuit imposes limits on how fast one can 406 deliver charge to facilitate polarization switching. In order to account for any such 407 effects, we normalized all measured switching times to the measured RC-time for 408 each device (Fig. 4d)[18], [24], thereby enabling us to make meaningful 409 410 comparisons across material systems (e.g. freestanding vs clamped films). Clear decreases in switching time persist even after such normalization, verifying that the 411 observed changes are from the mechanical clamping and not changes to extrinsic-412 413 circuit parameters. The normalized switching time, defined as the time when the switched polarization reaches 90% of its saturation value, normalized by the non-414 switching RC-time of the measurement circuit, was extracted for the samples with 415 thicknesses of 25 nm and 60 nm (Fig. 4d) with capacitors of the same area. The 416 freestanding membranes show a significant decrease in the switching time 417 compared to the clamped films. Particularly, the 60-nm-thick sample presents a 418 \sim 63% decrease in the switching time after lift-off. To quantitatively determine the role 419 of clamping from the switching dynamics measurements, we employ Merz' law[49] to 420 extract the ratio of the activation voltage for the clamped and freestanding films, 421 taking care to account for RC effects in the measurement circuit. Our findings (Fig. 422 4d) shows that the activation voltage for the 25-nm-thick clamped film is 3.45 V while 423

the 25-nm-thick membrane film has an activation voltage of 2.18 V, indicating that the removal of clamping effects results in a $\approx 37\%$ reduction in switching energy. This finding is consistent with the considerable decrease observed in coercive voltage in the hysteresis loops (**Fig 4a,b**) and energy barrier in our thermodynamic calculations (**Fig 2**), showing best agreement with "weak strain + tilt" clamping scenario.



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Figure 4. Ferroelectric switching voltage and switching dynamics of BFO films 431 and membranes. Ferroelectric polarization versus voltage (P-V loops) of 100nm (a.) 432 and 35nm (b.) clamped films and membranes measured at 10 kHz. c. Switching 433 dynamics as a function of applied voltage for the clamped and free-standing 25nm 434 films. d., Comparison of the extracted switching time (normalized by the RC-time 435 constant) of the samples before (clamped) and after lift-off (freestanding), with BFO 436 thicknesses of 25nm and 60nm. Solid lines and activation voltages (α) are shown for 437 fits to the Merz' law for the 25nm films. These findings show a ~40% reduction in 438 switching energy stemming from substrate clamping effects. 439

440 Finally, we performed time-resolved phase-field simulations (Methods,[33]) to

further investigate the relevant energy scales and the effects of clamping during 441 switching. We simulated the same applied voltage (13V) for both the clamped and 442 membrane cases, and the evolution of elastic, electric, and Landau energy during 443 the switching process (2000 time steps) were computed[50], [51] (Fig. 5). All 444 simulations start from an equilibrium domain state (Methods) with polarization 445 pointing downwards. A positive voltage is then applied on top (with the bottom 446 grounded) to switch the polarization upwards. Changes in the various energy values 447 correspond to changes in the polarization distribution within the simulation, with the 448 most dramatic changes occurring as domains are switched. We can clearly see that 449 the time for a freestanding membrane to switch (~200 timesteps) is significantly 450 shorter than that for the clamped film to switch (~800 timesteps). Corroborating the 451 452 true dynamic nature (opposed to quasi-static) of the experiment is the remarkable agreement between reductions in switching time predicted (~63% for the 60nm film, 453 and ~75% as predicted by simulation). Returning now to the fundamental aim of this 454 paper, by examining the time-resolved evolution of the elastic, electric, and Landau 455 energies individually (Fig 5a-c), we use our simulations to directly interrogate the 456 role of substrate clamping during switching. As expected, the elastic energy of the 457 membrane (Fig. 5a) is essentially negligible throughout the ferroelectric switching 458 process, except for small local stresses imposed by adjacent domains. The time-459 resolved elastic energy of the clamped film, on the other hand, remains high, and 460 locally peaks just before switching is completed. These results demonstrate that 461 dynamic evolution of the polar state and accompanying structural distortions 462

transiently modify the energy landscape. Since both nucleation and growth of 463 reverse polarized domains are activated processes[49] and both have exponential 464 dependence on the activation energy, such transient changes (even moderate) in the 465 energy landscape can have a dramatic effect on switching time. Other energy terms 466 (Landau and electric) are also impacted by mechanical constraints, where the high 467 elastic energy slows the evolution of the polarization so that the higher energy state 468 persists for a longer period of time. Finally, we address the role of oxygen octahedral 469 tilting. The data presented (Fig. 5) includes dynamical evolution of the oxygen 470 471 octahedral tilts, and as such, an associated energy increase (Equation 1). Informed by our earlier findings that the switching energy barrier lies somewhere between 472 strain clamping and strong strain + tilt clamping (*i.e.* weak strain + tilt clamping), and 473 474 to extract the effect on switching from the octahedral tilts, we simulate the same polarization switching (Fig. S11) without consideration of the oxygen octahedral tilts. 475 There is a stark contrast between these two cases, with the oxygen octahedral tilts 476 accounting for a ~10x increase in switching time over the case where oxygen 477 octahedral tilts are removed from the simulations. This is an important finding, and 478 the dramatic increase in switching time highlights the importance of proper 479 consideration of all coupled order parameters in setting the dynamics and energetics 480 of switching in BFO. 481



Figure 5. Free energy evolution during the switching process under an externally applied voltage for clamped film and membrane cases. Horizontal axis is the time in arbitrary unit (a.u.) and vertical axis is the average energy of the corresponding component within the whole simulation system in J m-3. **a.** Elastic energy. **b.** Electrostatic energy. **c.** Landau energy. **d.** Total free energy which is the summation of the elastic, electrostatic, and Landau energy. For the clamped film case, 0.4% compressive mismatch strain is considered.

In conclusion, our work reveals the fundamental role of substrate mechanical constraints in dictating ferroelectric switching energetics and dynamics in BFO, and more broadly, for displacive ferroelectric thin film materials in general. With the grand challenge of achieving sub-100mV switching in ferroelectrics, clamping effects and the relative contribution to switching energetics and dynamics of all coupled order parameters must be understood. We employ a Landau free energy formalism to

conduct thermodynamic calculations modeling varying degrees of clamping effects 497 from the substrate, both using ab-initio and phenomenological models. We 498 experimentally demonstrate a method of mitigating clamping effects by lifting-off 499 SRO/BFO/SRO trilayers from an STO substrate. Other methods, for example, by 500 tuning device aspect ratio[52] may provide additional pathways to mitigate clamping. 501 Here, we observe a marked evolution of crystal and domain structure, consistent 502 with changes in elastic constraints, and show that the energetics and dynamics of 503 the system drastically change after lift-off. We observe a significant reduction in 504 switching voltage and improved switching speeds for freestanding membranes 505 relative to clamped films. The origins of the changes observed are better understood 506 with the help of phase-field simulations, where the dynamic elastic energy and 507 oxygen octahedral tilts play a predominant role in slowing polarization reversal. 508

509

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528 Methods

Thermodynamic calculations. The calculations of free-energy profiles are performed using in-house code for solving the system of equations $\frac{\partial \varphi_i}{\partial t} = -L_{\varphi} \frac{\partial f}{\partial \varphi_i}$, [53] where *f* is defined by Equation 1 (Main text), φ_i is the order parameter and L_{φ} is the kinetic coefficient describing the rate at which φ approaches its equilibrium value. Since, in these simulations, we are only interested in the equilibrium values of the order parameters and not the trajectory by which it is reached, the values of L_{φ} are set to 1 in the reduced units (we checked that the choice of L_{φ} does not affect the

resulting equilibrium state of the system).

⁵³⁷ We perform the calculations of the free-energy profiles for the polarization switching ⁵³⁸ path in which 109° out-of-plane switch (P_y and P_z polarization components are ⁵³⁹ reversed) is followed by the 71° in-plane switch (P_x component is reversed). This ⁵⁴⁰ path is chosen based on PFM experiments on BFO/SRO heterostructures previously ⁵⁴¹ reported [14], in which the initial polarization switching event follows the ⁵⁴² aforementioned step sequence. In the following we will only discuss the 109° out-of-⁵⁴³ plane switch, though the same considerations can be applied to 71° in-plane switch.

For the freestanding BiFeO₃ membrane we assume that during the polarization switching process all order parameters can freely evolve and adapt to the instantaneous values of the switching polarization components. For example, for 109° out-of-plane switch, at each value of P_y=-P_z between -0.7 and 0.7 C/m², we allow P_x as well as of all the components of θ and the strain tensor, to evolve to their preferred values as dictated by $\frac{\partial \varphi_i}{\partial t} = -L_{\varphi} \frac{\partial f}{\partial \varphi_i}$. Then, we use the relaxed values of P, θ and strain to compute the energy of the system, at each step of the switch. For

completeness, the evolution of all order parameters with varied P_y is shown in **Fig. S12** of the Supporting Information (for a phase-field parameter set).

"Strain Clamped" vs. "Strain + Tilt Clamped". In the simulations of the films 553 clamped by the substrate, we consider three possible clamping effects. First, we 554 assume that the substrate clamps only $\epsilon_{11,}$ ϵ_{22} and ϵ_{12} components of the strain 555 tensor ("strain clamping" case). To reflect this in our simulations, we fix ϵ_{11} , ϵ_{22} and 556 ϵ_{12} to their equilibrium values corresponding to the initial direction of the polarization 557 and to the considered set of model parameters (either DFT or phase-field). Then, 558 similarly to the case of the freestanding membrane, for 109° out-of-plane switch we 559 vary P_y =- P_z components of the polarization between -0.7 and 0.7 C/m² and for each 560

561 P_y value we optimize P_x, θ_x , θ_y , θ_z as well as the unclamped components of the

strain tensor. The evolution of the order parameters with varying P_y is presented in **Fig. S12** of the Supporting Information together with that of freestanding case.

Next, we consider the possibility that the presence of the substrate can have an additional clamping effect on other order parameters, such as FeO₆ octahedral tilts ("strain+tilt clamping"). In particular, we study two cases, to which we refer in the following as "weak strain+tilt clamping" and "strong strain+tilt clamping". In the case of weak strain+tilt clamping, in addition to ϵ_{11} , ϵ_{22} and ϵ_{12} , we fix the non-switching components of polarization and tilts (Px and θ_x for 109° out-of-plane switch) to their initial equilibrium values. Then, we vary P_y =- P_z components and for each considered

⁵⁷¹ P_y value we optimize θ_y , θ_z as well as the remaining components of the strain tensor

 $(\epsilon_{33}, \epsilon_{13} \text{ and } \epsilon_{23})$. The evolution of all order parameters with Py is presented in Fig. 572 S13 of the Supporting Information. To simulate the case of strong strain+tilt 573 clamping, we first identify the equilibrium values of all order parameters for both sets 574 of the Landau potential coefficients (DFT and phase-field). Then, we vary P_{y} =- P_{z} and 575 θ_{v} =- θ_{z} between their equilibrium values corresponding to up and down polarization 576 directions while we keep P_x , θ_x , as well as ϵ_{11} , ϵ_{22} and ϵ_{12} fixed to their initial 577 values. For each value of P_v and θ_v we relax the unclamped components of the 578 strain tensor (ϵ_{33} , ϵ_{13} and ϵ_{23}). The evolution of the order parameters is shown in 579 Fig. S14 of the Supporting Information. 580

581

Film growth. The oxide heterostructures BFO/SRO/LSMO or SRO/BFO/SRO/LSMO 582 were grown on single-crystalline (001) STO substrate by pulsed laser deposition at 583 650-720 °C with focused laser fluence ~1.2 J cm⁻² in 100-160 mTorr oxygen pressure 584 and cooled down to room temperature in 400 Torr oxygen pressure. To protect the 585 film during the lift-off process, a 20-nm Pt layer was deposited on top of the SRO or 586 BFO layer by magnetron sputtering. The top SRO layer was patterned into circular 587 top electrode and the bottom SRO layer served as a bottom electrode for 588 ferroelectric switching testing. 589

590

Lift-off process. PDMS stamps were cut into 8 mm x 8 mm x 1.5 mm from a commercial specimen (Gelfilm from Gelpal). Then they were stacked tightly onto the film. After floating the PDMS/films in an etching solution (low-concentration HCI solution (0.3 vol %) mixed with 0.1 mol mL⁻¹ potassium iodide) for several hours, the LSMO dissolved to lift the freestanding film off STO substrate, which were washed with deionized water and dried with N₂ gas. The samples were then moved onto Si/Pt substrate. The entire stack was annealed at 110 °C for 30 min to promote adhesion at the film/new substrate interface. After cooling to 70 °C and peeling off the PDMS stamp with tweezers, the transferred membrane on Si/Pt substrate was obtained.

601

X-ray diffraction (XRD) and reciprocal space mapping (RSM). The films before and after lift-off were measured with a Panalytical Empyrean diffractometer (Cu-K α_1 , 1.540598 Å), using a hybrid, two-bounce primary monochromator on the incident beam. RSM of the samples were acquired with the same incident beam optics and a PIXcel^{3D} position-sensitive detector, using the frame-based 1D mode with a step time of 10 s.

608

Piezoresponse force microscopy (PFM). PFM was performed with an Atomic
 Force Microscope (Asylum Research Cypher, Santa Barbara, CA), conductive AFM
 probe (Nanoandmore, DT-NCHR, Watsonville, CA) with the DART mode. The typical
 contact resonance frequency is 260 kHz and its higher harmonics.

613

Polarization testing. For polarization switching measurements (P-V loops), we used
the patterned circular top electrodes with diameter of 16 µm at the frequency of 1 Hz100 kHz at both room temperature and 100 K with Precision Multiferroic tester
(Radiant Technologies).

618

619 **Phase-field simulation**. The current phase-field model for ferroelectric free standing 620 film is an extension to our previous model for bulk and epitaxial thin film simulations[32], [33], [51], [54], [55] in which we use the spontaneous polarization $p=(p_1, p_2, p_3)$ and oxygen octahedral tilt $\theta = (\theta_1, \theta_2, \theta_3)$ as the order parameters . A temporal evolution of the order parameters can be obtained by solving the timedependent Ginzburg-Landau equation [56], [57]:

625
$$\frac{\partial p_i}{\partial t} = -L_p \frac{\delta F_{\text{tot}}}{\delta p_i}$$
, (*i*=1, 2, 3) (2)

626
$$\frac{\partial \theta_i}{\partial t} = -L_{\theta} \frac{\delta F_{\text{tot}}}{\delta \theta_i}$$
, (*i*=1, 2, 3) (3)

in which L_p and L_{θ} are the kinetic coefficients, *t* is time, F_{tot} is the total free energy of BFO membrane. Owing to the lack of experimental data to which to fit L_p and L_{θ} , we set both L_p and L_{θ} to be 1 after normalizing all coefficients to unitless values. The expression for the total free energy is given as:

631 $F_{tot} = \iiint_{V_{BFO}} (f_{land} + f_{grad} + f_{elec} + f_{elast}) dV$. All equations with repeating subscripts 632 follow the Einstein summation notation, and the comma in subscript means spatial 633 differentiation, e.g. $p_{i,j} = \frac{\partial p_i}{\partial x_j}$.

 $f_{Land} = \alpha_{ij} p_i p_j + \alpha_{ijkl} p_i p_j p_k p_l + \beta_{ij} \theta_i \theta_j + \beta_{ijkl} \theta_i \theta_j \theta_k \theta_l + t_{ijkl} p_i p_j \theta_k \theta_l$ represents 634 the local free energy density, which includes the landau energy for polarization, 635 and the coupling terms, $f_{grad} = \frac{1}{2}g_{ijkl}p_{i,j}p_{k,l} +$ oxygen octahedral tilt 636 $\frac{1}{2}\kappa_{ijkl}\theta_{i,j}\theta_{k,l}$ represents the gradient energy, which includes the gradient energy for 637 both polarization and oxygen octahedral tilt, $f_{elec} = -\frac{\varepsilon_0 \varepsilon_{ij}^b}{2} E_i E_j - E_i p_i$ is the 638 electrostatic energy, where ϵ^b_{ij} is the background dielectric constant[58]–[61], E_i is the 639 electric field obtained by solving the electrostatic equilibrium equation $\varepsilon_0(\varepsilon_{11}^b \frac{\partial^2 \phi}{\partial x^2} +$ 640 $\varepsilon_{22}^{b}\frac{\partial^{2}\Phi}{\partial y^{2}} + \varepsilon_{33}^{b}\frac{\partial^{2}\Phi}{\partial z^{2}}) = \frac{\partial p_{1}}{\partial x} + \frac{\partial p_{2}}{\partial y} + \frac{\partial p_{3}}{\partial z}$, Φ is the electrical potential, and $f_{elast} =$ 641 $\frac{1}{2}C_{ijkl}(\varepsilon_{ij}-\varepsilon_{ij}^0)(\varepsilon_{kl}-\varepsilon_{kl}^0)$ is the elastic energy, in which ε_{ij} is the total strain 642 distribution obtained by solving the mechanical equilibrium equation $\sigma_{ij,j} = 0$, $\sigma_{ij} =$ 643 $C_{ijkl}(\varepsilon_{kl}-\varepsilon_{kl}^0)$, and the eigenstrain is connected to the order parameters $\varepsilon_{ij}^0=$ 644

 $\lambda_{ijkl}\theta_k\theta_l + Q_{ijkl}p_kp_l$. There are two differences between our free-standing film and our epitaxial thin film model[33], both of which pertain to solving for the mechanical equilibrium state. First, the clamped thin film has a fixed displacement bottom and traction-free top surfaces, while for the free-standing film, both the top and bottom surfaces are set as traction-free boundaries, as shown in equation (4) owing to the nature of the freestanding membrane,

651
$$\begin{cases} \sigma_{i3}|_{z=0} = 0\\ \sigma_{i3}|_{z=h_f} = 0, \\ \end{bmatrix}$$
 (i=1,2,3) (4)

where h_f means the membrane thickness. Second, the in-plane macroscopic strain in clamped thin film is controlled by the misfit of the substrate, while for the free-standing film, the in-plane macroscopic strain is set to be the average eigenstrain calculated from the current order parameter distribution, since overall the free-standing film is in a stress-free state.

We start our simulation from random noise for both the polarization and oxygen 657 octahedral tilt in a 128 nm * 128 nm * 30 nm (each simulation grid $\Delta x = 1 \text{ nm}$) 658 thick clamped thin film with 0.4% compressive biaxial misfit and 0 applied 659 electric field. The system is relaxed to an equilibrium state as shown in Figure 660 3(d). Then the same domain structure is used as an input to the free-standing 661 film simulation without applied electric field, from which we get the domain 662 structure of Figure 3(e). Next, starting from this equilibrium state, we first apply 663 an instantaneous negative electric potential, -10V, on both films' top surface 664 (bottom grounded) to pole the system fully upwards, then remove the potential 665 to relax the system back to equilibrium. The domain state at this stage is 71 666 stripe domains in the clamped film and single domain in the free-standing film. 667 Finally, an instantaneous 13V electric potential is applied on both films' top 668 669 surface (bottom still grounded) to switch the domains downwards, during which process we keep track of the energy evolution as shown in Figure 5. 670

The film thickness is 30 nm, or 30 layers of grid points, for both the clamped and

672	free-standing film. In the clamped film case, there are 6 layers of grid points of
673	air layer above and 10 layers of grid points of substrate layer below the film
674	along the z direction. While in the free-standing film case, there are 6 layers of
675	grid points of air layer above and 0 layer of grid point of substrate layer below
676	the film. More details regarding our numerical simulations and all physical
677	parameters in the above equations are listed in the Supporting Information.
678	
679	Data availability
680	The data that support the findings of this study are available from the corresponding
681	authors upon reasonable request.
682	
683	Competing interests
684	The authors declare no competing interests.
685	

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